



Advanced Thin Film Technologies

Dr. Detlef Theirich

WS 2026/2027

Information also on our website www.lfeb.uni-wuppertal.de

Starting date: Tuesday 20.10.2026 at 2:15 p.m. in the seminar room FG-01.01

Time / Place: Tuesday 2:15 – 5.45 pm, expected seminar room FG-01.01

These times can be adjusted on 20.10.2026 in agreement with the participants if necessary.

This lecture is aimed at:

Students of the **Master Smart Materials and System** in the specialization area Materials and Fundamentals

Students of the **Master Elektrotechnik** in the specialization area Polymer Electronics and Novel Technologies; area Materials and Processes.

Students of the **Master Wirtschaftsingenieurwesen Energiemanagement** in the compulsory elective area Energy Management 2; area Energy Systems and Components.

Students of the **Master Wirtschaftsingenieurwesen Informationstechnik** in the compulsory elective area of Electronics.

Students of the **Master Maschinenbau** in the compulsory elective area of Materials Science and Materials Engineering.

Content:

Introduction and repetition

Plasma

Selected deposition techniques (Sputtering, reactive sputtering, CVD and plasma CVD, ALD and plasma ALD)

Thin film properties and how process parameters affect these properties

Selected methods for thin film characterization

Industrial equipment and application examples

Dr. Detlef Theirich